

said target being manufactured homogeneously of said sputtering material,

C<sup>1</sup> said [generally] disk-shaped section defining threaded holes proximate said outer periphery of said disk-shaped section.

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C<sup>2</sup> 10. (Amended) The target of claim 9 wherein said [generally] disk-shaped section is sufficiently self-supporting to bear stress arising when said section is mounted to said vacuum chamber supported only proximate said outer periphery, and said chamber is evacuated to initiate sputtering, such that one [generally] planar surface of said section is exposed to vacuum pressure while an opposite side thereof is not exposed to reduced pressure.

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C<sup>3</sup> 12. (Amended) The target of claim 9 wherein said sputtering material is one of Titanium, Gold, [or] and Aluminum.

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C<sup>4</sup> 23. (Amended) The target of claim 9 wherein said [generally] disk-shaped section defines threaded holes [in] opening into said at least one radially-inward step, proximate said outer periphery of said disk-shaped section.